							SHEE	1 1 OF 1	
INFORMATION DISCLOSURE CITATION IN AN OUPE APPLICATION				ATTY. DOCKET NO 60188-589		SERIAL NO. 10/620,430			
PEC 1 8 2003				APPLICANT Kaoru INOUE, et	APPLICANT Kaoru INOUE, et al.				
(PTO-1449)				FILING DATE July 17, 2003	GR	GROUP 2825			
U.S. PATENT DOCUMENTS									
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Codez (# known)	Publication Da MM-DD-YYYY		of Patentee or Applicant of Cited Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear				
		US							
	100	US							
		US							
		US	<u> </u>						
	 	US				<u> </u>			
ļ	-	US			•	 			
		us		*		1			
:		US							
	-	US				 			
·		US							
		US		- 					
		US							
		US							
FOREIGN PATENT DOCUMENTS									
EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes -Number 4 -Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documer	nt Where Re	ges, Columns, Lines Translation Where Relevant Figures Appear			
<u> </u>			ļ	<u>.</u>	-		Yes	No	
		<u>. </u>	 		+				
			 						
						-			
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)									
EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where							
YXX		C.F. Lin et al., Improved Contact Performance of GaN Film Using Si Diffusion:, 2000 American Institute of Physics, Applied Physics Letters, Vo. 76, No. 14, pp. 1878-1880, April 3, 2000							
18k		Hiroyuki MASATO et al., "Novel High Drain Breakdown Voltage AlGaN/GaN HFETs Using Selective Thermal Oxidation Process", IEEE, IEDM 16.2.1-16.2.4, pp. 377-380, 2000							
b./	Bally & EXAMINER 07/13/04								
10000	in the	luan			7				

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 809. Oraw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.